

Phosphorus Trifluoride, PF₃

Description

At room temperature and atmospheric pressure, Phosphorus Trifluoride (PF₃) is a colorless, non-fuming, poisonous gas. In the semiconductor industry, PF₃ is used for ion implantation and etching.

Properties	Units	Specifications
Phosphorus Trifluoride, PF ₃		99.9%
Air	(ppmv)	<50
Hydrogen Fluoride, HF	(ppmv)	<100
Nitrogen, N ₂	(ppmv)	<50
Oxygen/Argon, O ₂ / Ar	(ppmv)	<50

For specific values or requirements, please contact us.

About Inhance Technologies

Inhance Technologies is a leading provider of specialty chemicals, gases and material technologies in a wide range of industries, across four continents.

For more than 40 years, Inhance Technologies' world-class experts have been collaborating with customers globally to create customized solutions and offer exclusive technologies.